

**Electronic Patent Application Fee Transmittal**

<b>Application Number:</b>	10564510			
<b>Filing Date:</b>	12-Jan-2006			
<b>Title of Invention:</b>	POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN			
<b>First Named Inventor/Applicant Name:</b>	Yasuo Masuda			
<b>Filer:</b>	Neil S. Bartfeld/Jennifer Dolan			
<b>Attorney Docket Number:</b>	SHIGA7.036APC			
Filed as Large Entity				
<b>U.S. National Stage under 35 USC 371 Filing Fees</b>				
<b>Description</b>	<b>Fee Code</b>	<b>Quantity</b>	<b>Amount</b>	<b>Sub-Total in USD(\$)</b>
<b>Basic Filing:</b>				
<b>Pages:</b>				
<b>Claims:</b>				
<b>Miscellaneous-Filing:</b>				
<b>Petition:</b>				
<b>Patent-Appeals-and-Interference:</b>				
<b>Post-Allowance-and-Post-Issuance:</b>				
Utility Appl issue fee	1501	1	1510	1510
Publ. Fee- early, voluntary, or normal	1504	1	300	300

Description	Fee Code	Quantity	Amount	Sub-Total in USD(\$)
<b>Extension-of-Time:</b>				
<b>Miscellaneous:</b>				
Printed copy of patent - no color	8001	10	3	30
<b>Total in USD (\$)</b>				<b>1840</b>